

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) An exposure apparatus comprising:
a substrate table that is movable while holding a substrate;
an optical member that forms a pattern onto the substrate on the substrate table through a liquid which at least partially fills a space between the optical member and the ~~substrate; substrate, the liquid only partially covering the substrate; and~~
a correcting device that corrects a positional deviation occurring in at least one of the substrate on the substrate table and the substratetable, the positional deviation being caused by supply of the liquid.
2. (Previously Presented) The exposure apparatus of Claim 1, the apparatus further comprising:
a position measuring device that obtains positional information of the substrate table, wherein
the correcting device corrects a positional deviation occurring in at least one of the substrate and the substrate table according to the position of the substrate tablewhich is obtained by the position measuring device.
3. (Previously Presented) The exposure apparatus of Claims 2, wherein
the correcting device corrects an error in the positional information in at least one of the substrate and the substrate table obtained directly or indirectly by the position measuring device, which occurs due to supply of the liquid.
4. (Previously Presented) The exposure apparatus of Claim 1, wherein
the correcting device corrects a positional deviation that occurs by a change in the shape of the substrate table.

5. (Previously Presented) The exposure apparatus of Claim 1, wherein the substrate table has a fiducial member used for position setting, and the correcting device corrects a positional deviation between the fiducial member and the substrate.
6. (Previously Presented) The exposure apparatus of Claim 1, wherein the correcting device corrects the distance between the optical member and the substrate in an optical axis direction of the optical member.
7. (Previously Presented) The exposure apparatus of Claim 1, wherein the correcting device corrects the positional deviation according to a physical quantity related to the liquid.
8. (Previously Presented) The exposure apparatus of Claim 7, wherein the physical quantity related to the liquid includes at least one of pressure of the liquid and surface tension of the liquid.
9. (Previously Presented) The exposure apparatus of Claim 1, wherein the correcting device corrects a positional deviation that occurs by vibration of the substrate table.
10. (Previously Presented) The exposure apparatus of Claim 1, the apparatus further comprising:
 - a mask stage on which a mask having the pattern formed is mounted that can be moved holding the mask; and
 - the correcting device corrects the positional deviation by changing a thrust given to at least one of the substrate table and the mask stage.
11. (Previously Presented) The exposure apparatus of Claim 10, wherein the correcting device comprises a controller that changes the thrust by feedforward control.

12. (Previously Presented) The exposure apparatus of Claim 1, wherein the correcting device corrects the positional deviation based on position obtaining results of a transferred image of the pattern transferred on the substrate.
13. (Previously Presented) The exposure apparatus of Claim 1, wherein the correcting device corrects the positional deviation based on simulation results.
14. (Previously Presented) A stage device that has a substrate table which movably holds a substrate whose surface is supplied with a liquid, the device comprising:
a position measuring device that obtains positional information of the substrate table; and
a correcting device that corrects a positional deviation occurring in at least one of the substrate on the substrate table and the substrate table, the positional deviation being caused by supply of the liquid, wherein
an immersion area is defined by an area where the liquid is located, and the immersion area is smaller than the surface of the substrate on the substrate table.
15. (Previously Presented) The stage device of Claim 14, wherein the correcting device corrects a positional deviation that occurs by a change in the shape of the substrate table.
16. (Previously Presented) The stage device of Claim 14, wherein the substrate table has a fiducial member used for position setting, and the correcting device corrects positional deviation between the fiducial member and the substrate.
17. (Currently Amended) An exposure method which forms a pattern onto a substrate held by a substrate table, the method comprising:

detecting a change that occurs in at least one of the substrate and the substrate table caused by supply of a liquid; and

forming the pattern onto the substrate based on results of the detecting a change, by irradiating a radiation beam through an optical member and the liquid which at least partially fills a space between the optical member and the substrate on the substrate table-table, the liquid only partially covering the substrate.

18. (Previously Presented) The exposure method of Claim 17, wherein the forming the pattern is performed with at least one of a positional deviation that occurs by a change in the shape of the substrate table and the distance between the optical member and the substrate in an optical axis direction of the optical member corrected.

19. (Previously Presented) The exposure method of Claim 17, wherein the detecting a change detects a change according to a physical quantity related to the liquid, and the forming the pattern is performed with the change according to the physical quantity related to the liquid corrected.

20. (Previously Presented) The exposure method of Claim 19, wherein the physical quantity related to the liquid includes at least one of pressure of the liquid and surface tension of the liquid.

21. (Previously Presented) The exposure method of Claim 17, wherein the forming the pattern is performed with a positional deviation that occurs by vibration of the substrate table corrected.

22. (Previously Presented) The exposure method of Claim 17, wherein the forming the pattern is performed with the change corrected by changing a thrust given to at least one of the substrate table and a mask stage on which a mask where the pattern is formed is mounted.

23. (Previously Presented) The exposure method of Claim 22, wherein the change of the thrust is performed by feedforward control.
24. (Previously Presented) The exposure method of Claim 17, wherein the change is corrected based on position obtaining results of a transferred image of the pattern transferred on the substrate.
25. (Previously Presented) The exposure method of Claim 17, wherein the change is corrected based on simulation results.
26. (Previously Presented) The exposure apparatus of Claim 1, wherein supply of the liquid in the space between the optical member and the substrate is performed by a liquid supply device, and the liquid supply device supplies the liquid to a part of the substrate.
27. (Previously Presented) The exposure apparatus of Claim 1, wherein the substrate table has a holding member that holds the substrate and plate members arranged in the periphery of the holding member.
28. (Previously Presented) The exposure apparatus of Claim 2, wherein the position measuring device obtains positional information of the substrate table without involving the liquid.
29. (Previously Presented) The stage device of Claim 14, wherein supply of the liquid to the substrate is performed by a liquid supply device, and the liquid supply device supplies liquid to a part of the substrate.
30. (Previously Presented) The stage device of Claim 14, wherein the substrate table has a holding member that holds the substrate and plate members arranged in the periphery of the holding member.
31. (Previously Presented) The stage device of Claim 14, wherein

the position measuring device obtains positional information of the substrate table without involving the liquid.

32. (Previously Presented) The exposure method of Claim 17, wherein the liquid is supplied to a part of the substrate.
33. (Previously Presented) The exposure method of Claim 17, wherein on the substrate table, plate members are arranged in the periphery of a holding member that holds the substrate.
34. (Previously Presented) The exposure apparatus of Claim 1, wherein an immersion area is defined by an area where the liquid is located and the immersion area is smaller than a surface of the substrate held by the substrate table.
35. (Previously Presented) The exposure apparatus of Claim 34, wherein the immersion area is movable on the surface of the substrate in accordance with the movement of the substrate table.
36. (Previously Presented) The stage device of Claim 14, wherein the immersion area is movable on the surface of the substrate in accordance with the movement of the substrate table.
37. (Previously Presented) The exposure apparatus of Claim 17, wherein an immersion area is defined by an area where the liquid is located and the immersion area is smaller than a surface of the substrate held by the substrate table.
38. (Previously Presented) The exposure method of Claim 37, wherein the immersion area is movable on the surface of the substrate in accordance with the movement of the substrate table.
39. (Previously Presented) A stage device comprising:

a table that is movable while holding an object whose surface is supplied with a liquid, wherein an immersion area where the liquid is located is smaller than the surface of the object held by the table;

a position measuring device that obtains positional information of the table;

and

a control device that obtains a positional deviation related to the positional information of the table obtained by the position measuring device, the positional deviation being caused by supply of the liquid.

40. (Previously Presented) The stage device of Claim 39, wherein the control device obtains the positional deviation according to a property of the liquid.

41. (Previously Presented) The stage device of Claim 40, wherein the property includes at least one of pressure of the liquid, surface tension of the liquid, a flow of the liquid, and a contact angle of the liquid.

42. (Previously Presented) The stage device of Claim 40, further comprising: a memory that stores a relation between the property and the positional deviation.

43. (Previously Presented) The stage device of Claim 39, wherein the table has a fiducial member used for position setting of the table, and the control device obtains a positional deviation between the fiducial member and the object held by the table.

44. (Previously Presented) An exposure apparatus comprising: a stage device according to Claim 39, wherein the object is a substrate; and an optical member that forms a predetermined pattern on the substrate.